

# Thickness shear mode BAW resonator based on epitaxial (10 $\bar{1}2$ ) LiNbO $_3$ / (11 $\bar{2}0$ ) AZO / (10 $\bar{1}2$ ) Al $_2$ O $_3$

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## 1. Introduction

LiNbO $_3$  crystal is suitable for SAW filter applications because of their high  $Q$  and electromechanical coupling coefficient  $k$ . However, LiNbO $_3$  films have not been successful in the BAW industry because thickness extensional mode  $k_t^2$  in the easily grown c-axis oriented LiNbO $_3$  film is significantly low ( $k_t^2 = 4\%$ ), as shown in Fig. 1. To obtain high electromechanical coupling, quasi-shear mode  $k_{35}^2$  in the 168° Y-cut LiNbO $_3$  is the best candidate as shown in Fig. 1. Therefore, the mechanical thinning of bulk LiNbO $_3$  single crystal plate has been used to obtain the thin single crystalline layer for BAW resonators.<sup>1-4</sup> However, the wafer size of these top-down process is limited to 6 inch which is the size of the bulk LiNbO $_3$  single crystal wafer. In contrast, bottom-up process such as sputtering growth is well-developed in the 8 inch wafer such as AlN films. For bottom-up process, Park's group achieved the epitaxial growth of (10 $\bar{1}2$ ) LiNbO $_3$  films on (10 $\bar{1}2$ ) Al $_2$ O $_3$  single crystal substrate.<sup>5</sup> In order to estimate electromechanical coupling and to characterize resonator properties of (10 $\bar{1}2$ ) LiNbO $_3$  layer, epitaxial bottom electrode layer is required. In this study, we reported the epitaxial growth of (10 $\bar{1}2$ ) LiNbO $_3$  on epitaxial (11 $\bar{2}0$ ) Al doped conductive ZnO layer (AZO)/(10 $\bar{1}2$ ) Al $_2$ O $_3$  substrate. Shear mode acoustic properties of the resonator were then investigated.

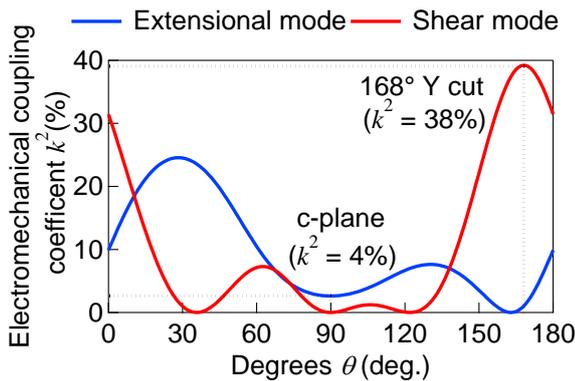


Fig. 1 Thickness extensional mode and shear mode electromechanical coupling  $k^2$  as a function of angle in LiNbO $_3$ .

## 2. Crystallographic orientation

The epitaxial film resonators for (10 $\bar{1}2$ ) LiNbO $_3$  film was fabricated by RF magnetron

sputtering technique. The resonator has with Au film / epitaxial (10 $\bar{1}2$ ) LiNbO $_3$  film (900 nm) / (11 $\bar{2}0$ ) Al doped conductive ZnO layer (AZO) / (10 $\bar{1}2$ ) Al $_2$ O $_3$  substrate (0.5 mm) structure. The crystalline properties were evaluated by the X-ray diffraction. Fig. 2 show the XRD patterns of AZO layer and LiNbO $_3$  layer of (10 $\bar{1}2$ ) LiNbO $_3$  films, respectively. (10 $\bar{1}2$ ) LiNbO $_3$  peak and (11 $\bar{2}0$ ) AZO were clearly observed. Rocking curve FWHM of (11 $\bar{2}0$ ) AZO layer and (10 $\bar{1}2$ ) LiNbO $_3$  layer was found to be 1.5° and 5.7°, respectively.

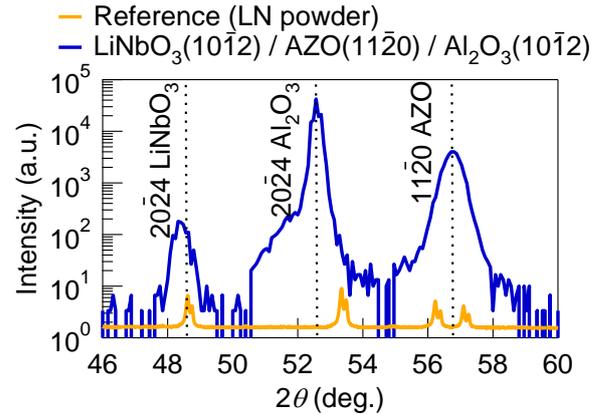


Fig. 2  $2\theta$ - $\omega$  scan XRD patterns of epitaxial (10 $\bar{1}2$ ) LiNbO $_3$  film / (11 $\bar{2}0$ ) AZO / (10 $\bar{1}2$ ) Al $_2$ O $_3$  substrate.

The epitaxial growth of the (10 $\bar{1}2$ ) LiNbO $_3$  resonator was investigated by the of (10 $\bar{1}4$ ) XRD pole figure. LiNbO $_3$  XRD peak was expected to appear near the Al $_2$ O $_3$  peak because their crystal structures were based on trigonal system. Therefore, the XRD patterns of (10 $\bar{1}2$ ) LiNbO $_3$  resonator at  $\chi = 42^\circ$  were measured as shown in Fig. 3. LiNbO $_3$  XRD peak and Al $_2$ O $_3$  peak are successfully separated.

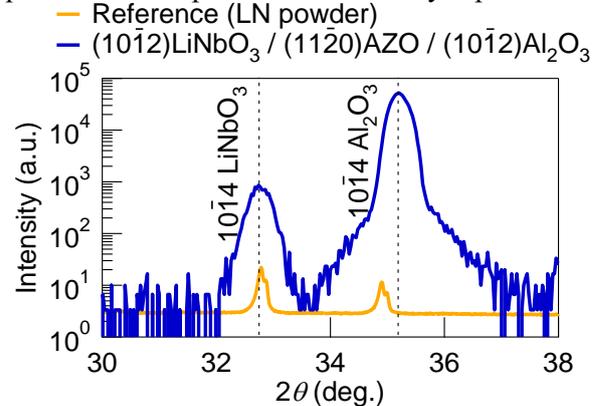


Fig. 3  $2\theta$ - $\omega$  scan XRD patterns ( $\chi = 42^\circ$ ) of epitaxial (10 $\bar{1}2$ ) LiNbO $_3$  film.

As shown in Fig. 4, pole concentration in the  $(10\bar{1}4)$  pole figure indicates epitaxial growth of  $(10\bar{1}2)$  LiNbO<sub>3</sub> film because two of the three-fold symmetry of the pole figure are observed.

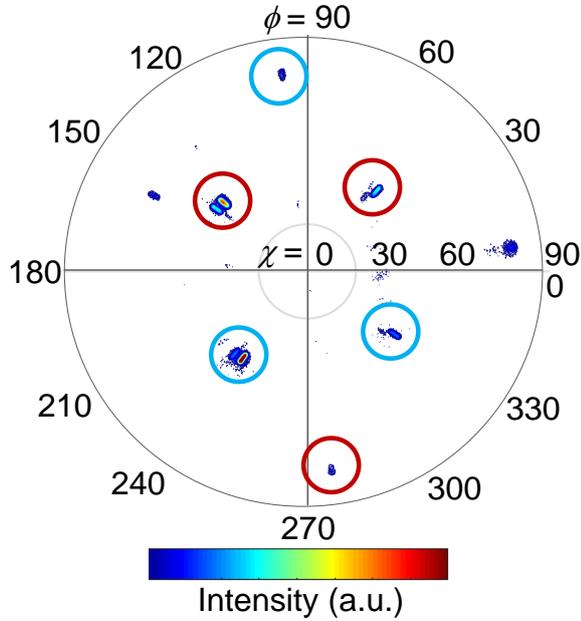


Fig. 4  $(10\bar{1}4)$  pole figure of epitaxial  $(10\bar{1}2)$  LiNbO<sub>3</sub> film/ $(11\bar{2}0)$  AZO /  $(10\bar{1}2)$  Al<sub>2</sub>O<sub>3</sub> substrate.

### 3. Impulse response

Piezoelectric properties of resonators were evaluated by time domain impulse responses and insertion loss. First,  $S_{11}$  were measured by network analyzer. The time domain impulse response was obtained by inverse Fourier transform of  $S_{11}$ . The time domain impulse response of the  $(10\bar{1}2)$  LiNbO<sub>3</sub> resonator was shown in Fig. 5. Time interval of longitudinal wave echo can be predicted from acoustic velocity and thickness of the substrate. From the result,  $(10\bar{1}2)$  LiNbO<sub>3</sub> resonator clearly excited the shear waves, as expected. Fourier transform of the response showed the quasi-shear mode operation of the LiNbO<sub>3</sub> layer in the 1.1 GHz.

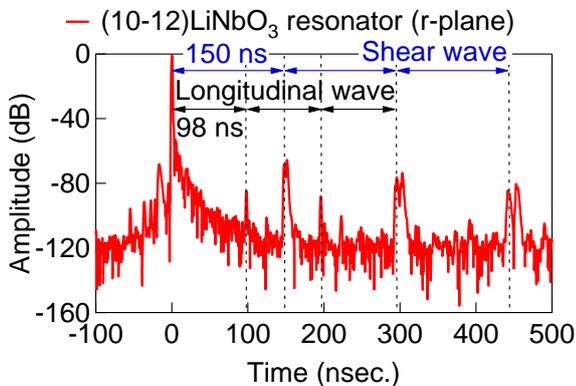


Fig. 5 The time domain impulse response obtained from an inverse Fourier transform of  $S_{11}$ .

### 4. Conclusions

We demonstrate the epitaxial growth of  $(10\bar{1}2)$  LiNbO<sub>3</sub> film by RF magnetron sputtering technique. The shear wave excitation was observed in the epitaxial  $(10\bar{1}2)$  LiNbO<sub>3</sub> film.

In the future, we would like to estimate an electromechanical coupling coefficient quasi-shear mode  $k_{35}^2$  in the epitaxial  $(10\bar{1}2)$  LiNbO<sub>3</sub> film

### Acknowledgment

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